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WHAT WE CLAIM IS:

polishing a workpiece, said chemical mechanical polishing

to cloth comprising, on an opposite-to-workpiece face thereof:

polishing projections having polishing faces arranged

to come in contact with a workpiece for polishing the same;

polishing agent passages, having bottoms, for

introducing a polishing agent; and

at least one-stage step portions formed between said polishing faces of said polishing projections and the bottoms of said polishing agent passages.

2. A chemical mechanical polishing cloth according to Claim 1, wherein:

said polishing cloth has a flat plate portion;
said polishing projections are formed as projecting
from said flat plate portion;

said polishing agent passages are formed by grooves
formed in said flat plate portion; and

the surface of said flat plate portion forms said step portions.

3. A chemical mechanical polishing cloth according to Claim 1, wherein:

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said polishing cloth has a flat plate portion;
said polishing projections are formed as projecting
from said flat plate portion, and include a plurality of
multi-stage projections having at least one-stage
difference-in-level faces and the top faces serving as said
polishing faces;

said polishing agent passages are formed by the spaces among said plurality of multi-stage projections; and

said difference-in-level faces form said step
10 portions.

4. A chemical mechanical polishing apparatus, comprising:

a chemical mechanical polishing cloth for chemically mechanically polishing a workpiece;

a polishing head for holding and rubbing a workpiece with said chemical mechanical polishing cloth; and

a polishing agent supply mechanism for supplying a polishing agent to said chemical mechanical polishing cloth,

said chemical mechanical polishing cloth including, on an opposite-to-workpiece face thereof:

polishing projections having polishing faces arranged to come in contact with a workpiece for polishing the same; polishing agent passages, having bottoms, for

25 introducing a polishing agent; and

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at least one-stage step portions formed between said polishing faces of said polishing projections and the bottoms of said polishing agent passages.

5. A chemical mechanical polishing apparatus according to Claim 4, wherein:

said polishing cloth has a flat plate portion;
said polishing projections are formed as projecting
from said flat plate portion;

said polishing agent passages are formed by grooves formed in said flat plate portion and

the surface of said flat plate portion forms said step portions.

6. A chemical mechanical polishing apparatus according to Claim 4, wherein:

said polishing cloth has a flat plate portion;
said polishing projections are formed as projecting
from said flat plate portion, and include a plurality of
multi-stage projections having at least one-stage
difference-in-level faces and the top faces serving as said
polishing faces;

said polishing agent passages are formed by the spaces among said plurality of multi-stage projections; and

said difference-in-level faces form said step

B

-portions.

add B3>